

**FEEDFORWARD CONTROL WITH REDUCED LEARNING TIME FOR
LITHOGRAPHIC SYSTEM TO IMPROVE THROUGHPUT AND
ACCURACY**

ABSTRACT OF THE DISCLOSURE

Embodiments of the present invention are directed to a control system and method for controlling the trajectory and alignment of one or more stages by incorporating a grouping method in the control methodology. In one embodiment, a method of controlling movement of one or more stages of a precision assembly to process a substrate having a plurality of process regions comprises dividing the substrate into blocks according to one or more preset criteria, each block of the substrate including one or more process regions; generating learning data for one or more representative process regions for each block of the substrate; and using the generated learning data of the one or more representative process regions of each block to control movement of the one or more stages to process the block of one or more process regions of the substrate.

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